

FORM PTO-1449

U.S. DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICE

ATTORNEY DOCKET NO. 4704/USA/ETCH/SILICON

SERIAL NO.

LIST OF ART CITED BY APPLICANT

(Use several sheets if necessary)

APPLICANT: Yuen et al.

FILING DATE: Herewith

GROUP: Unk

U.S. PATENT DOCUMENTS

Examiner Initial		DOCKET NUMBER							DATE	NAME	CLASS	SUBCLASS	FILING IF APPROPRIATE
<i>gag</i>	A1	4	2	8	2	2	6	7	08/04/81	Köyel	427	38	
	A2	4	4	3	3	2	2	8	02/21/84	Nishimatsu, et al.	219	10.55 R	
	A3	4	4	6	5	5	3	2	08/14/84	Fukano	156	643	
	A4	4	4	9	0	2	0	9	12/25/84	Hartman	156	643	
	A5	4	5	0	2	9	1	4	03/05/85	Trumpp et al.	156	643	
	A6	4	5	7	6	6	9	2	03/18/86	Fukuta, et al.	204	165	
	A7	4	7	0	5	5	9	5	11/10/87	Okudaira et al.	156	643	
	A8	4	7	3	8	7	4	8	04/19/88	Kisa	156	643	
	A9	4	7	8	6	3	5	2	11/22/88	Benzing	156	345	
	A10	4	8	1	8	3	2	6	04/04/89	Liu, et al.	156	345	
	A11	4	8	3	1	9	6	3	05/23/89	Saito, et al.	118	723	
	A12	4	8	6	3	5	6	1	09/05/89	Freeman, et al.	156	646	
	A13	4	8	6	7	8	4	1	09/19/89	Loewenstein, et al.	156	643	
	A14	4	8	7	6	2	1	2	10/24/89	Koury	437	34	
	A15	4	9	7	5	1	4	4	12/04/90	Yamazaki, et al.	156	643	
	A16	4	9	9	2	1	3	6	02/12/91	Tachi et al.	156	643	
	A17	4	9	9	4	4	1	0	02/19/91	Sun et al.	437	192	
	A18	5	0	0	2	6	3	2	03/26/91	Loewenstein, et al.	156	643	
	A19	5	0	1	3	3	9	8	05/07/91	Long et al.	156	643	
	A20	5	0	3	5	7	6	8	07/30/91	Mu et al.	156	626	
	A21	5	0	8	4	1	2	6	01/28/92	McKee	156	345	
	A22	5	0	9	4	7	1	2	03/10/92	Becker et al.	156	643	
	A23	5	1	1	0	4	0	8	05/05/92	Fujii et al.	156	643	
	A24	5	1	1	0	4	1	1	05/05/92	Long	156	656	
	A25	5	1	1	8	3	8	7	06/02/92	Kadomura	156	657	
	A26	5	1	5	8	6	4	4	10/27/92	Cheung, et al.	156	643	
	A27	5	1	6	0	4	0	7	11/03/92	Latchford et al.	156	656	
	A28	5	1	6	4	3	3	0	11/17/92	Davis et al.	437	192	
	A29	5	1	7	6	7	9	2	01/05/93	Fullowan et al.	156	652	
	A30	5	1	8	8	9	8	0	02/23/93	Lai	437	193	
<i>gag</i>	A31	5	1	9	2	7	0	2	03/09/93	Tseng	437	47	

EXAMINER

George Goudreau

DATE CONSIDERED

10-021

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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FORM PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE				ATTORNEY DOCKET NO. 4704/USA/ETCH/SILICON				SERIAL NO.: N/A				
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)										APPLICANT: Yuen et al.				1763
										FILING DATE: Herewith				
U.S. PATENT DOCUMENTS														
Examiner Initial	A	B	C	D	E	F	G	H	DOCKET NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
gag	A32	5	2	5	6	2	4	5	10/26/93	Keller, et al.	156	643		
	A33	5	2	8	1	3	0	2	01/25/94	Gabric, et al.	156	643		
	A34	5	2	8	2	8	9	9	02/01/94	Balmashonov, et al.	118	723 R		
	A35	5	3	1	2	5	1	9	05/17/94	Sakai, et al.	134	1		
	A36	5	3	1	8	6	6	8	06/07/94	Tamaki, et al.	156	662		
	A37	5	3	3	8	3	9	8	08/16/94	Szwejkowski, et al.	156	655		
	A38	5	3	5	4	4	1	7	10/11/94	Cheung, et al.	156	643		
	A39	5	3	5	6	4	7	8	10/18/94	Chen, et al.	134	1		
	A40	5	3	5	8	6	0	1	10/25/94	Cathey	156	656		
	A41	5	3	7	8	3	1	1	01/03/95	Nagayama, et al.	156	643		
	A42	5	3	8	2	3	1	6	01/17/95	Hills, et al.	156	643		
	A43	5	4	1	3	9	5	4	05/09/95	Aydil, et al.	437	81		
	A44	5	4	3	1	7	7	2	07/11/95	Babie, et al.	156	643.1		
	A45	5	4	4	3	6	8	6	08/22/95	Jones, et al.	216	37		
	A46	5	4	4	9	4	1	1	09/12/95	Fukuda, et al.	118	723 MP		
	A47	5	5	1	4	6	2	2	05/07/96	Bornstein, et al.	437	189		
	A48	5	5	2	1	1	1	9	05/28/96	Chen, et al.	437	187		
	A49	5	5	2	9	1	9	7	06/25/96	Grewal	216	68		
	A50	5	6	2	0	6	1	5	04/15/97	Keller	438	720		
	A51	5	6	2	6	7	7	5	05/06/97	Roberts, et al.	216	67		
	A52	5	6	4	4	1	5	3	07/01/97	Keller	257	324		
	A53	5	7	5	3	5	3	3	05/19/98	Saito	437	192		
	A54	5	7	5	6	4	0	0	05/26/98	Ye, et al.	438	710		
	A55	5	7	6	7	0	2	1	06/16/98	Imai, et al.	438	719		
	A56	5	7	8	8	7	9	9	08/04/98	Steger, et al.	156	345		
	A57	5	8	4	3	2	3	9	12/01/98	Shrotriya	134	1.1		
	A58	5	8	6	6	4	8	3	02/02/99	Shiau, et al.	438	720		
	A59	5	8	6	9	4	0	1	02/09/99	Brunemeier, et al.	438	710		
	A60	5	8	7	4	3	6	3	02/23/99	Hoh, et al.	438	721		
	A61	5	8	7	9	5	7	5	03/09/99	Tepman, et al.	216	68		
EXAMINER George Goudreau											DATE CONSIDERED 10-021			
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				FILING DATE: Herewith				
OTHER ART (Including Author, Title, Date, Pertinent Pages, etc.)								
	C1	Aydil, et al., "Multiple Steady States in a Radio Frequency Chlorine Glow Discharge," <u>J. Appl. Phys.</u> , Volume 69, No. 1, January 1, 1991, pages 109-114						
	C2	Hillenius, S.J., et al., "A Symmetric Submicron CMOS Technology," <u>IEEE</u> , pages 252-255, 1986						
	C3	PCT Search Report dated October 28, 1999.						
	C4	PCT Notification of International Search Report dated February 4, 1999						
	C5							
	C6							
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PENDING U.S. PATENT APPLICATIONS

ATTORNEY DOCKET NO.: 4704/USA/ETCH/SILICON
 SERIAL NUMBER: N/A
 FILING DATE: HERewith
 INVENTORS: YUEN, ET AL.

09-718,319

1763

EXAMINER INITIAL		PENDING U.S. PATENT APPLICATIONS
GAG	D1	U.S. Patent Application entitled, "Method for Improved Cleaning of Substrate Processing System"; filed July 11, 1997; Serial No. 08/893,922; Inventors: Kao, et al.
	D2	U.S. Patent Application entitled, "Apparatus for Improved Remote Microwave Plasma source for Use with Substrate Processing Systems"; filed April 23, 1997; Serial No. 08/839,111; Inventors: Kao, et al.
	D3	U.S. Patent Application entitled, "Method and Apparatus for Determining the Endpoint in a Plasma Cleaning Process"; filed July 2, 1997; Serial No. 08/887,165; Inventors: Subrahmanyam, et al.
	D4	U.S. Patent Application entitled, "Apparatus and Method for Efficient and Compact Remote Microwave Plasma Generation"; filed April 22, 1997; Serial No. 08/839,007; Inventor: Bhatnagar
	D5	U.S. Patent Application entitled, "Method and Apparatus for Pre-stabilized Plasma Generation for Microwave Clean Applications"; filed November 13, 1996; Serial No. 08/746,658; Inventors: Fong, et al.
	D6	U.S. Patent Application entitled, "Inductively Coupled HDP-CVD Reactor"; filed May 29, 1997; Serial No. 08/865,018; Inventors: Redeker, et al.
	D7	U.S. Patent Application entitled, "Symmetric Tunable Inductively Coupled HDP-CVD Reactor"; filed July 15, 1996; Serial No. 08/679,927; Inventors: Redeker, et al.
	D8	U.S. Patent Application entitled, "Apparatus and Methods for Upgraded Substrate Processing System with Microwave Plasma Source"; filed March 5, 1997; Serial No. 08/811,627; Inventors: Tanaka, et al.
GAG	D9	U.S. Patent Application entitled, "Microwave Apparatus for In-situ Vacuum Line Cleaning for Substrate Processing Equipment"; filed October 30, 1996; Serial No. 08/741,241; Inventors: Pang, et al.
	D10	
	D11	
	D12	
	D13	
	D14	George Goudreau 10-021